



<b>Form 1449 (Modified)</b>  <b>Information Disclosure Statement By Applicant</b>  (Use Several Sheets if Necessary)	Atty Docket No.      Application No.: NOVL085/NVLS-2875      10/785,235  Applicant: Wang et al. Filing Date      Group February 23, 2004 <del>2812</del> 2823
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**U.S. Patent Documents**

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
FLT	A1	4,882,008	1/21/89	Garza et al.			
FLT	A2	6,329,017	12/11/01	Lu et al.			
FLT	A3	2004/0099952	05/27/04	Goodner et al.			
FLT	A4	2004/0102031	05/27/04	Kloster et al.			
FLT	A5	2004/0185679	09/23/04	Ott et al.			
	A6						
	A7						
	A8						
	A9						
	A10						
	A11						

**Foreign Patent or Published Foreign Patent Application**

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
							Yes	No
	B1							

**Other Documents**

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
FLT	C1	Tipton et al., "Method For Removal Of Porogens From Porous Low-K Films Using Supercritical Fluids", U.S. Patent No. 10/672,305, filed September 26, 2003, Office Action dated March 22, 2005
Examiner /Fernando L. Toledo/		Date Considered 11/14/2006

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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	Applicant:	
	Wang et al.	
	Filing Date	Group
	HEREWITH 2/23/04	<del>Unassigned</del> 2823

### U.S. Patent Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
FLT	A1	6,329,017	12/11/01	Liu et al.			
	A2	6,383,466	5/7/02	Domansky et al.			
	A3	6,365,266	4/2/02	MacDougall et al.			
	A4	5,504,042	4/2/96	Cho et al.			
	A5	5,858,457	1/12/96	Brinker et al.			
	A6	6,270,846	8/7/01	Brinker et al.			
	A7	6,387,453	5/14/02	Brinker et al.			
	A8	6,420,441	10/10/99	Allen et al.			
	A9	6,271,273	10/10/00	You et al.			
	A10	4,885,262	12/5/89	Ting et al.			
	A11	5,686,054	11/11/97	Barthel et al.			
	A12	5,851,715	12/22/98	Barthel et al.			
	A13	6,140,252	10/31/00	Cho et al.			
	A14	6,392,017	5/21/02	Chandrashekar			
	A15	6,386,466	5/14/02	Ozawa et al.			
	A16	4,357,451	11/2/82	McDaniel			
	A17	6,479,374	11/12/02	Ioka et al.			
✓	A18	6,548,113	4/15/03	Birnbaum et al.			

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							Yes	No
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### Other Documents

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
FLT	C1	Liu et al., "Mesoporous Silica Film From a Solution Containing a Surfactant and Methods of Making Same," U.S. Patent Application Publication No. US2002/0034626, Published March 21, 2002, 27 Pages
FLT	C2	Wu et al., "Use of Multifunctional SI-Based Oligomer/Polymer for the Surface Modification of Nanoporous Silica Films," U.S. Patent Application Publication No. US2002/0001973, Published January 3, 2002, 13 Pages
FLT	C3	Cho et al., "Plasma Treatments of Molecularly Templated Nanoporous Silica Films," Electrochemical and Solid-State Letters, 4 (4) G35-G38 (2001)

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FLT	C4	Justin F. Gaynor, "In-Situ Treatment of Low-K Films With a Silylating Agent After Exposure To Oxidizing Environments," U.S. Patent Application No.10/056,926 filed January 24, 2002, 34 Pages
FLT	C5	Gangpadhyay et al., "The First International Surface Cleaning Workshop," Northeastern University, November 11-14, 2002
FLT	C6	Yung et al., "Spin-on Mesoporous Silica Films with Ultralow Dielectric Constants, Ordered Pore Structures, and Hydrophobic Surfaces," Adv. Mater. 2001, 13, No. 14, 1099-1102
FLT	C7	Schulberg et al., "System for Deposition of Mesoporous Materials," U.S. Patent Application No. 10/295,965, filed November 15, 2002, 64 Pages
FLT	C8	Watkins et al., "Mesoporous Materials and Methods," U.S. Patent Application No.10/301,013, filed November 21, 2002, 34 Pages
Examiner /Fernando L. Toledo/		Date Considered 11/14/2006

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